

# **Aluminium promoted sulfidation of ammonium perrhenate: presence of nanobattery in the ReS<sub>2</sub> composite material based memcapacitor**

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## ***Abstract:***

*This study demonstrates a new approach to the synthesis of rhenium disulfide (ReS<sub>2</sub>) in a sulfidation reaction of ammonium perrhenate (NH<sub>4</sub>ReO<sub>4</sub>), occurring at room temperature and in water solution. It was found that aluminum (Al) plays a catalytic role in the reaction taking place in low ionic strength solutions. The reaction product is characterized using several analysis techniques, including energy dispersive X-ray spectroscopy (EDX), X-ray photoelectron spectroscopy (XPS), X-ray diffraction (XRD), transmission electron microscopy (TEM), Raman*

*spectroscopy and thermogravimetric analysis (TGA). Furthermore, an interesting observation of both memristive and memcapacitive effects, existence of nanobattery with an electromotive force estimated to be 0.80V, in a prototypical device based on the as-synthesized ReS<sub>2</sub> composite material is presented. This finding shows promise for the implementation of the ReS<sub>2</sub> in the next generation memristor technology.*

**Key words:** rhenium disulfide, bipolar resistance switching, memcapacitor, nanobattery

## **1. Introduction**

Rhenium disulfide (ReS<sub>2</sub>) belongs to the class of 2 dimensional transition metal dichalcogenides (2D TMDs) [1], and is an emerging semiconductor due to its distinguishable properties in the aspect of not only its anisotropy, chemical stability, or mechanical flexibility but also the possibility to tune its properties with doping or the prospects of its integration with other 2D heterostructures for functional devices fabrication [2-6]. Accordingly, among a large number of reports concerning electronic devices based on diverse TMDs [7-9], the ReS<sub>2</sub> was demonstrated to have a great potential for utilization in the field effect transistors, photodetectors, digital logic, and energy storage devices [4, 10-15]. Furthermore, for the first time, an interesting effect of the negative differential resistance has been recently reported in a phosphorene/ReS<sub>2</sub> heterojunction based device [16]. Among them, other types of TMDs such as 1T-TaS<sub>2</sub>, MoS<sub>2</sub> and n-doped MoS<sub>2</sub>-polyvinylpyrrolidone (PVP) nanocomposite [17-21] exhibited resistance switching characteristic. Memristor principle of operation is based on the phenomenon of resistance change of the device active material, which is desirable from the perspective of their application in the emerging, next generation memory storage technology (memristor technology). In order to meet the requirements of modern electronics, only the

memristors of excellent performance and low cost of fabrication of active materials, used for their construction, can be considered for utilization in the industry [22]. A key role in the development of the high-performance memristor is the search for, design and synthesis of materials exhibiting desirable properties. However, a limited number of reports regarding resistive switching, identified in TMDs or their composites, points on the still initial stage of their implementation [17-21]. Till the present day, many of the reported devices can't meet the criteria for data storage in modern electronics. Consequently, a search for novel composite materials is necessary and of great importance to carry out further theoretical and experimental studies.

Despite a number of well explored routes leading to the synthesis of  $\text{ReS}_2$ , such as mechanical cleavage [23], liquid or chemical exfoliations [24, 25], and chemical vapour deposition (CVD) [4, 26] methods, to the best of our knowledge, there is limited number of scientific studies presenting bulk synthesis of the  $\text{ReS}_2$  achieved *via* sulfidation processes of Re precursors. Above mentioned methods are not ideal as they either rely on complex processes requiring high vacuum and elevated temperatures, or harsh chemical reaction environment. Considering previous reports, we can see dependence, to a large degree, of the sulfidation processes of the  $\text{NH}_4\text{ReO}_4$  or  $\text{Re}_2\text{O}_7$  precursors on the temperature, content of water, or the necessity of a catalyst use to obtain satisfactory reaction efficiency [27-29]. For comparison, introduced here sulfidation process is not only based on the cost effective one pot synthesis, carried out from water soluble precursors taking place at room temperature and ambient pressure but also is inherently scalable. In addition, this approach extends the scope of available soft chemical synthesis methods of  $\text{ReS}_2$  allowing its easy adaptation for large scale production.

This study demonstrates intriguing electronic properties of the fabricated device utilizing the ReS<sub>2</sub> based composite material, which has been synthesized using bottom-up chemical synthesis method. The synthesis leads to a product in a bulk quantity thus allows its easy integration into electronic devices *via* solution processing techniques. It was found that the room temperature sulfidation process occurs due to the catalytic properties of aluminum (Al). Most likely, it is facilitated by adsorption of ReO<sub>4</sub><sup>-</sup> ions on the Al catalyst surface, for which the activation energy of the reaction is lowered as a consequence of the Re–O bonds polarization. A detailed characterization of the synthesis product has been performed using combination of spectroscopy techniques, including Raman, infrared (IR), energy dispersive X-ray (EDX), X-ray photoelectron (XPS) spectroscopy, as well as transmission electron microscopy (TEM), thermogravimetric analysis (TGA) and differential scanning calorimetry (DSC). Moreover, we provide experimental evidence of the coexistence of both resistive and capacitive effects identified in one device, based on the as-synthesized ReS<sub>2</sub> composite material. The preliminary electric characterization of the device was carried out, and the possible mechanisms of the observed dual resistive and capacitive memory effects were briefly presented and discussed. Those extraordinary properties of ReS<sub>2</sub> composite material are of great significance and interest from the research and industrial communities, due to the possibilities of its utilization in devices of novel functionalities, beyond what was accomplished up to the present moment, such as reconfiguration architectures [30], neuromorphic computing [31] and artificial synapses [32].

## **2. Materials and Methods**

### *2.1. Materials*

Ammonium perrhenate (NH<sub>4</sub>ReO<sub>4</sub>, purity ≥ 99.9%) was provided by Sigma Aldrich (Shanghai, China). Sodium sulfide nonahydrate (Na<sub>2</sub>S·9H<sub>2</sub>O, purity ≥ 98%), acetone, ethyl and isopropyl

alcohol were purchased from Keshi Chemical Company (Chengdu, China). The chemicals were used without further purification. Aluminum pellets (purity of 99.999%) were provided by Alfa Aesar.

### *2.2. Aluminium catalyst preparation*

Aluminum film (thickness ~400 nm) was prepared by physical vapour deposition (PVD) method on a glass substrate in a vacuum chamber (Xiwoke Co., China). Prior to the experiment, the glass substrates were cleaned with ethyl and isopropyl alcohol by treatment in an ultrasonication bath for 5 min, and finally dried in a flow of high purity N<sub>2</sub> gas.

### *2.2. ReS<sub>2</sub> synthesis procedure*

The synthesis was performed under an ambient atmosphere (temperature 22°C, humidity ~70%). First, the Al/glass substrates were cleaned three times with ethyl and isopropyl alcohol by treatment in an ultrasonication bath for 5 min, and dried in a flow of high purity N<sub>2</sub> gas. In separate glass vessels, the NH<sub>4</sub>ReO<sub>4</sub> (0.19 mmol) and Na<sub>2</sub>S·9H<sub>2</sub>O (0.38 mmol) compounds were dissolved in 1.8 and 1.0 mL of water, respectively. In the next step, both solutions were mixed and directly transferred using micropipette on the Al/glass substrate. Immediately, a formation of gas bubbles and the dark brown product was observed. The reaction propagated until the Al film was completely dissolved in the highly alkaline reaction environment. Nevertheless, the reaction could be continued by transfer of the reaction mixture onto another fresh Al/glass substrate. Finally, the reaction product was purified in water using a molecular porous membrane (MWCO 8 kDa), collected by centrifugation and dried at room temperature.

### *2.3. ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al device fabrication*

First, the substrates of indium tin oxide (ITO, 200 nm) on glass were patterned using photolithography method. Prior to the device fabrication, the ITO/glass substrates were cleaned

three times in acetone, ethyl and isopropyl alcohol by treatment in an ultrasonication bath (10 min), and dried in a flow of high purity N<sub>2</sub> gas. The water:ethyl alcohol suspension (v/v, 1:0.1, concentration 1.7 mg/mL) of as-synthesized ReS<sub>2</sub> was prepared by ultrasonication (1 h), and used to form the active layer by spin coating process (500 rpm, 30 s) on the cleaned ITO/glass substrates. In the final step, the aluminum top electrode (thickness ~110 nm) was deposited by thermal evaporation in a PVD chamber, under vacuum of 10<sup>-4</sup>-10<sup>-3</sup> Pa.

### **3. Results**

#### *3.1 Compositional and structural analysis*

##### *3.1.1 EDX analysis*

First of all, the compositional and elemental analyses of the synthesis product were conducted using an energy dispersive X-ray (EDX) spectroscopy method. Figure S1 of the electronic supporting information (ESI) shows the EDX results indicating the presence of rhenium (Re), sulfur (S), carbon (C) and oxygen (O) atoms in the examined sample. Based on the atomic percentages of the elements, the ratio of S and Re was estimated to be ReS<sub>2.46</sub>. Additionally, elemental mapping and several SEM images of the synthesis product are presented in Figure S2.

##### *3.1.2 XPS analysis*

The bonding configurations of the Re and S atoms were examined by recording high-resolution 4f and 2p XPS spectra of ReS<sub>2</sub>, respectively. After the peak deconvolution procedure, data shown in Figure 1A, we could identify two doublets located at the binding energies (BEs) of 42.38 and 44.78 eV. These BEs are characteristic for the 4f<sub>7/2</sub> spin-orbit split doublet of Re in the Re<sup>4+</sup>, corresponding to the ReS<sub>2</sub> [4] and in the Re<sup>6+</sup> oxidation state [33], respectively. Deconvolution of the high resolution 2p spectrum of S (Figure 1B), revealed a complex environment composed of four characteristic doublets corresponding to the core 2p<sub>3/2</sub> level peaks

of S in the form of sulfide ( $S^{2-}$ , assigned to terminal S atoms in polysulfides  $S_n^{2-}$ ) located at 161.74 eV [34], disulfide ( $S_2^{2-}$ ) at 162.96 eV [4], sulfinyl ( $SO^{2-}$ ) [35] located at 166.29 eV and sulfate ( $SO_4^{2-}$ ) at 167.98 eV [36]. We are convinced that other S containing surface bounded species, such as: sulfur (IV) oxide ( $SO_2$ ) [35], methylsulfonyl ( $SO_2CH_3$ , 168.0 eV) [37], thiosulfate ( $S_2O_3^{2-}$ , 167.7 eV) [35], or persulfate ( $S_2O_8^{2-}$ , 168.10 eV) [38] might contribute to the S 2p peaks of the highest BE values. In comparison to the EDX results, the XPS analysis indicated a slightly higher ratio of Re:S estimated to be 1:2.7, which is most likely associated with an overlap of the  $S_2^{2-}$  2p<sub>3/2</sub> peak with the one representing central S atoms in  $S_n^{2-}$  [34]. The high resolution spectrum of carbon (C 1s, Figure S3A of the ESI), shows several peaks typical for a carbonaceous matter occurring as a surface overlayer.

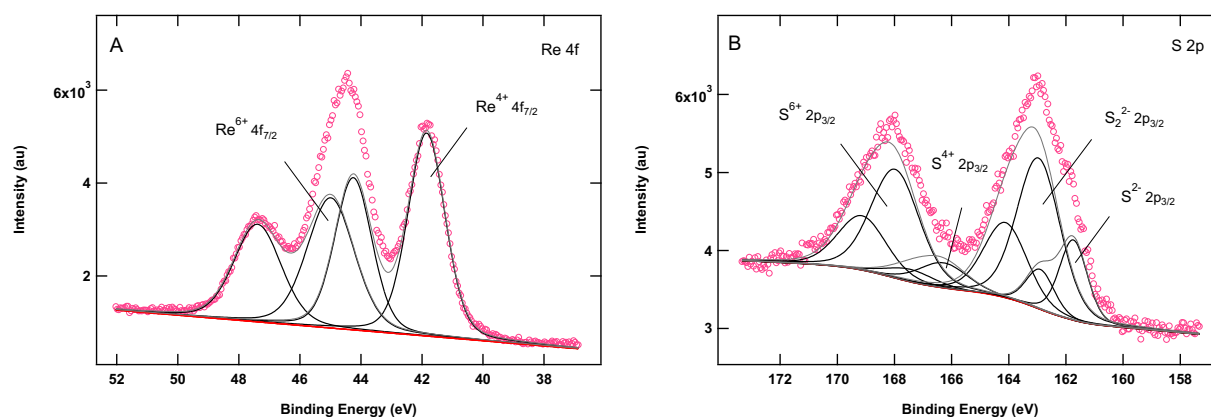


Figure 1 High resolution XPS spectra of A) Re 4f and B) S 2p, recorded at an emission angle normal to the sample surface.

For these species, the deconvolution procedure indicated emissions from various functional groups, such as adventitious carbon (C–H, C–C at 284.62eV), hydroxyl, ether or C–S group (C–OH, C–O–C at 286.54 eV), and ester or acid functional group (O–C=O at 288.48eV) [39]. Furthermore, extended delocalized electrons resulted in photoelectron plasmon loss feature peaks ( $\pi-\pi^*$  transition peaks) located at 291.75 and 294.39 eV, demonstrating that the  $sp^2$  bonds are

dominant in the surface C layer [40]. The relative peak intensity ratios were estimated to be 96.13 % (at 284.6 eV) and 3.87 % (at 285.15 eV) for  $sp^2$  and  $sp^3$  bonded C, respectively. Noteworthy, the  $\pi-\pi^*$  transition peaks are absent in the C 1s XPS spectrum of the unpurified product (Figure S3B), indicating an occurrence of secondary reactions of the surface atoms with various water dissolved molecules (mostly  $CO_2$  and CO). The high resolution oxygen spectrum (O 1s, Figure S3C of the ESI) demonstrates peaks corresponding to O in the form of metal oxide (O–O at 530.00 eV), hydroxyl and organic C–O groups (C–OH, C–O at 531.75 eV) as well as a carbonyl group together with surface adsorbed water (C=O,  $H_2O$  at 533.10 eV) [39]. Additionally, in the spectrum of the purified sample (Figure S4) we can observe an appearance of nitrogen (N 1s, 400.47 eV) peak (assigned to C–N bonding) [41], originating from the sample surface atoms reaction with water dissolved gaseous  $N_2$  or nitrogen oxides.

### 3.1.3 XRD analysis

The XRD pattern of the as-synthesized  $ReS_2$  with assigned major Bragg reflections is presented in Figure 2. The diffraction peak assignment is in agreement with the reference pattern of triclinic  $ReS_2$  and fall under the space group  $P\bar{1}$  (JCPD 82-1379) [2]. The fitted peak position values are collected in Table S1 (ESI). In comparison to the reference lattice spacing [2], we can notice a slight expansion of the (100), (01-2) and (1-21) lattice planes of 0.02, 0.19 and 0.18 Å, and a contradiction of the (001) lattice plane of 0.14 Å. These observable changes in the distances between the lattice planes can be explained by taking under consideration the synthesis method, where imperfect stacking of the  $ReS_2$  layers could result from the surface covered with a noticeable amount of diverse C species (see Figures S3A and B of the ESI) or inorganic impurities. Additionally, from the process of chemical synthesis, we can expect foreign atoms



inclusion in the lattice of the ReS<sub>2</sub> crystal, or stress resulting from the deformation of ReS<sub>2</sub> layers [42, 43].

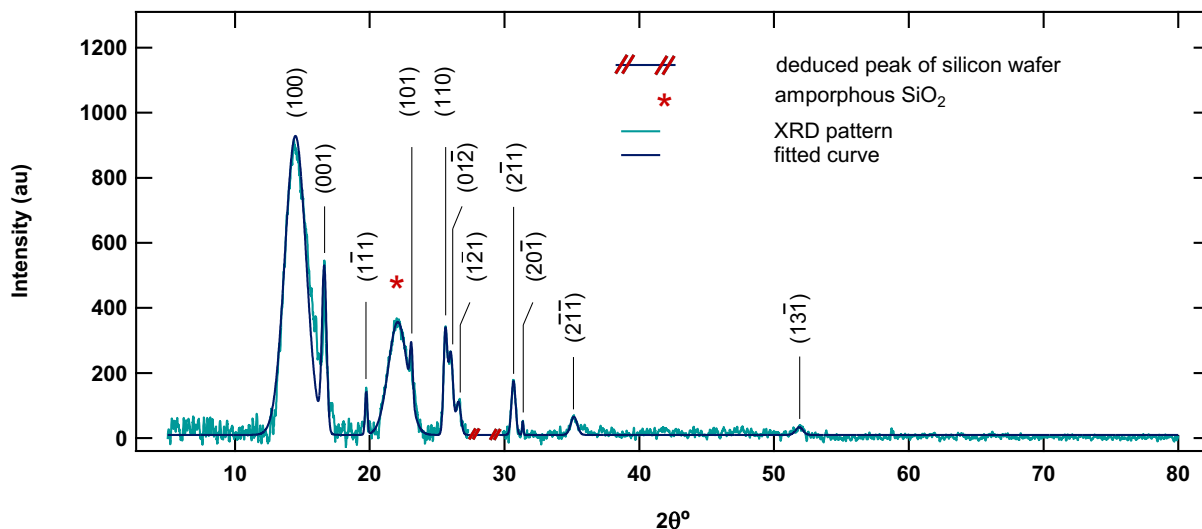
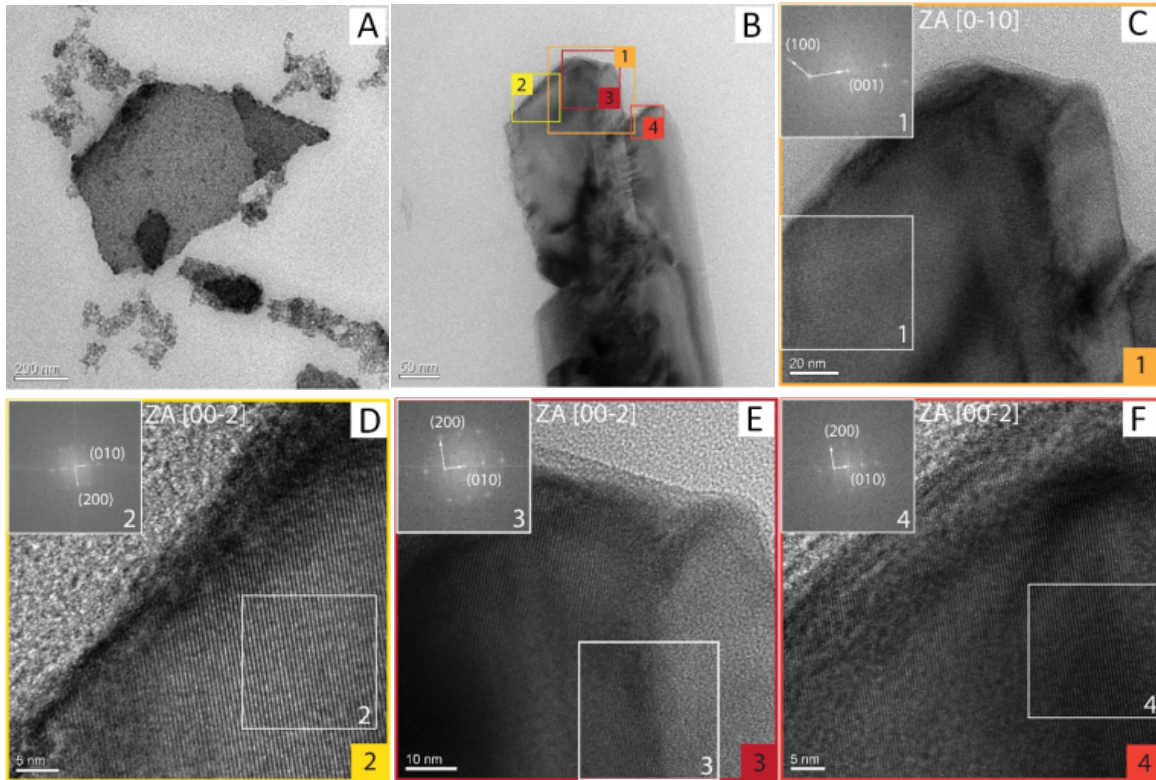


Figure 2 XRD pattern of ReS<sub>2</sub> with assigned crystallographic indices.

### 3.1.4 TEM analysis

Supporting the XRD results, several TEM images of ReS<sub>2</sub> have been acquired as shown in Figure 3. Figure 3C-F present high resolution TEM (HR TEM) images, taken from the areas indicated by squares (labeled in Figure 2B from 1 to 4), with the corresponding images from the Fast Fourier Transform (FFT) analysis [Insets 1-4, Figure 3C-F] of the ReS<sub>2</sub> crystal. The diffraction spots were assigned to (100), (010) [Figure 3C] and (200), (010) [(Figure 3D-F)] planes of reflection confirming crystalline nature of the product.



**Figure 3.** A-F) TEM images of ReS<sub>2</sub>; and G-J) HR TEM images of ReS<sub>2</sub> acquired from areas 1-4, indicated by squares in (F) and centered at the [0-10] (G) and [00-2] (H-J) zone axis. Insets: Images of FFT analysis acquired from areas 1-4.

### 3.1.5 Raman spectroscopy analysis

An undistorted tetrahedral ( $T_d$  point group symmetry)  $\text{ReO}_4$  molecule exhibits four fundamental Raman modes [44]. However, the symmetry of  $T_d$  coordinated  $\text{ReO}_4^-$  molecules confined to a crystalline lattice is lower than  $T_d$ , due to molecule distortions arising from the need of its accommodation to the lattice structure. The distortions cause a shift of the bands frequency values, as well as a split of the band representing bending modes. Due to the aforementioned, in the case of  $\text{NH}_4\text{ReO}_4/\text{Al}$  (Figure 4A curve (a)), we can observe lower symmetry surface coordinated  $\text{ReO}_4^-$  molecules and in effect more complicated Raman spectrum.

Based on the reference frequency values, we could assign the bands to the Re=O symmetric stretching mode at  $967.85 \pm 0.02 \text{ cm}^{-1}$ , antisymmetric stretching mode that splits into two peaks at  $915.73 \pm 0.13$  and  $893.28 \pm 0.13 \text{ cm}^{-1}$ , as well as to the lifted degeneracy of the Re–O bending mode giving rise to bands at  $343.09 \pm 0.17$ ,  $335.23 \pm 0.31$  and  $328.49 \pm 0.45 \text{ cm}^{-1}$  [44, 45].

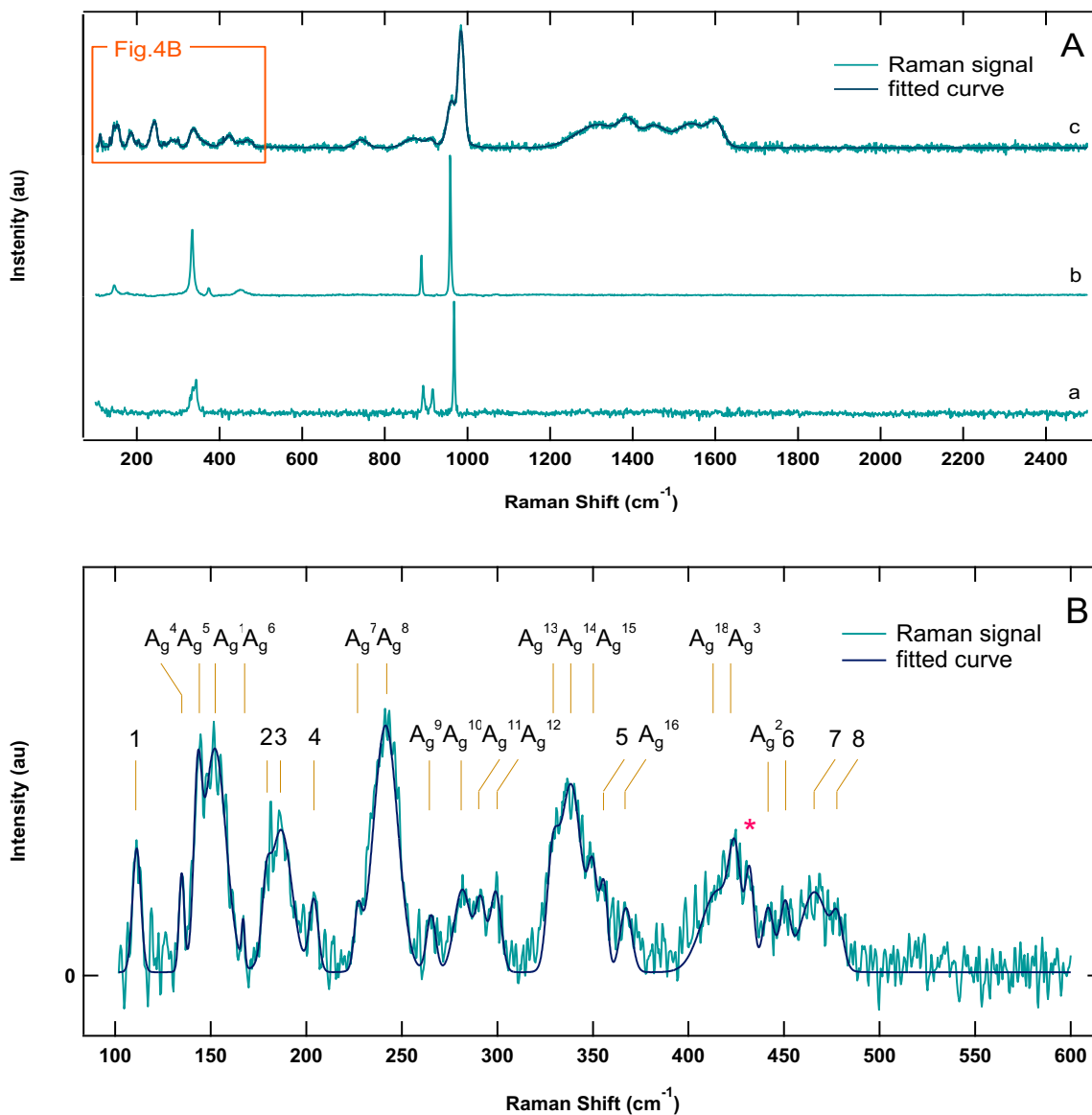


Figure 4 A) Raman spectrum recorded at ambient conditions for curve: a)  $\text{NH}_4\text{ReO}_4/\text{Al}$ , b) synthesis product before purification, and c) purified product; B) low frequency Raman spectrum of the purified product.

In the case of the Raman spectrum recorded for the synthesis product before purification (Figure 4A curve (b)), we can notice not only a significant change in the relative intensities of the bands in a high frequency region but also slight shift in their frequencies of antisymmetric ( $888.57 \pm 0.05$  and  $925.80 \pm 1.59 \text{ cm}^{-1}$ ) and symmetric ( $958.56 \pm 0.01 \text{ cm}^{-1}$ ) stretching modes of the Re–O in  $\text{ReO}_4^-$  molecules, indicating change in their symmetry. In addition to the lower frequency bending modes at  $333.8 \pm 0.05$  and  $373.99 \pm 0.33 \text{ cm}^{-1}$ , we notice newly appeared lattice vibration modes at  $145.9 \pm 0.35$  and  $176.01 \pm 0.76 \text{ cm}^{-1}$  [44, 45]. Taking under account the composition of the examined sample, the weak peak at  $176.01 \pm 0.76 \text{ cm}^{-1}$  might indicate presence of the Re–O–Re linkages [44], and together with the broadened peak, centred at  $451.51 \pm 0.93 \text{ cm}^{-1}$  (composed of overlapped peaks between  $436.06$  and  $476.05 \text{ cm}^{-1}$ ), at the same time it can be related to the S–S stretching and lattice modes of the  $\text{S}_2^{2-}$  anion or higher polysulfide anions ( $\text{S}_n^{2-}$ ), respectively [46]. We also observe peaks at  $145.9 \pm 0.35$  and  $218.28 \pm 1.23 \text{ cm}^{-1}$  associated with the Re in-plane vibrations in  $\text{ReS}_2$  [47].

An observable change in the Raman spectrum recorded for the purified product can be seen in Figure 4A curve (c). Most importantly, the bands between  $888.57$  and  $958.56 \text{ cm}^{-1}$  (present in Figure 4A curves (a) and (b)) were replaced by two broad bands centred at  $742.93 \pm 0.60$ ,  $870.54 \pm 1.08$  and  $909.93 \pm 0.71 \text{ cm}^{-1}$ , which could be ascribed to the Re–O stretching modes similar to those observed in low symmetry rhenium (VI) oxide ( $\text{ReO}_3$ ) [48, 49], but at the same time the peak at  $870.54 \pm 1.08 \text{ cm}^{-1}$  might represent the vibrations of the Re–O–Re linkages ( $\text{ReO}_3\text{–O–ReO}_3$  in  $\text{Re}_2\text{O}_7$ ), accompanied by overlapped and broadened bands at  $\sim 465$  and  $\sim 180 \text{ cm}^{-1}$  (bands 2-4 and 6-8, Figure 4B) [44]. The lowest frequency band (indicated as 1, Figure 4B) most probably corresponds to the lattice vibrations of  $\text{ReO}_4^-$  [45]. The higher intensity narrow bands at  $960.53 \pm 0.17$  and  $984.87 \pm 0.06 \text{ cm}^{-1}$  originate from the symmetric Re=O bond

stretching vibrations [50]. It is worth to mention, that bands located at  $\sim 240$ , 350, 470, 750, 885 and  $992\text{ cm}^{-1}$  have been also identified in the  $\text{ReO}_3$  films deposited by evaporation in the reducing environment [51]. The ambiguity of the bands assignment should be interpreted not only based on the existence of the Re–O bonding in diverse configuration but also complex coordination geometry of the molecules.

Interestingly, the Raman spectrum of the purified sample shows characteristic pattern exhibiting broadened and overlapped peaks centered at  $1380.30 \pm 0.75$  and  $1575.10 \pm 0.47\text{ cm}^{-1}$  (for details on the bands location see Table S2, ESI), featuring the D and G bands of C characteristic for all poly-aromatic hydrocarbons [52]. The main G band represents in-plane  $\text{sp}^2$  C–C stretching mode (in both rings and chains) [53] and appears for all  $\text{sp}^2$  C systems, including amorphous carbon, carbon nanotubes, and graphite, with the alteration of the line shape depending on the material quality [54]. The D band is due to the breathing modes of  $\text{sp}^2$  C atoms in rings attributed to the presence of structural defects [52, 53, 55]. Raman spectra of C films are dominated by the  $\text{sp}^2$  C sites, as a result of a visible excitation that always resonates with the  $\pi$  states. For this reason, even for a substantial amount of amorphous  $\text{sp}^3$  C the visible Raman analysis portrays  $\text{sp}^2$  vibrations. The  $\text{ReS}_2$  surface coverage with diverse compounds (see XPS analysis for details), led in some cases to the significant broadening and overlapping of Raman bands at low frequencies. Nonetheless, low frequency peaks corresponding to the  $\text{ReS}_2$  have been identified by carrying multiple peak fitting procedure of the acquired spectrum. The result is presented in Figure 4B, with the corresponding fitted frequency values collected in Table S2 (ESI).

The Raman peaks indexing of the  $\text{ReS}_2$  (Figure 4B) has been borrowed from McCreary et al. [47]. Accordingly, the  $A_g^1$  corresponds to a single in-plane mode of the  $\text{ReS}_2$  with all vibrations

parallel to the plane, the out-of-plane S atoms vibrations are represented by the  $A_g^2$ , and quasi-out-of-plane vibrations of S atoms, at slight angles with respect to the basal plane, are indicated by the  $A_g^3$  mode. Other identified modes can be ascribed to the vibrations of atoms at varying angles as a consequence of lower crystal symmetry of the ReS<sub>2</sub>. The low frequency  $A_g^4$  mode represents predominately Re out-of-plane vibrations, Re in-plane vibrations are assigned as the  $A_g^1$ ,  $A_g^6$ ,  $A_g^7$ , and  $A_g^8$ . Finally, the S vibrations in the ReS<sub>2</sub> are indicated as the  $A_g^2$ ,  $A_g^3$ , and modes from  $A_g^9$  to  $A_g^{18}$  [47]. The frequency distributions of the assigned modes are in agreement with those obtained in earlier studies [47, 56]. Nonetheless, slight shifts of the peak frequencies can be explained considering the synthesis method, where various surface molecules and impurities may influence the frequencies of atoms vibrations.

### 3.1.6 IR spectroscopy analysis

The mid-infrared spectrum is presented in Figure 5. Correspondingly, the first weak band at 3739.89 cm<sup>-1</sup> is related to the H<sub>2</sub>O vibration modes [57], meanwhile, the broad peak centered at 3411.11 cm<sup>-1</sup> indicates the presence of exchangeable protons, typically from the H<sub>2</sub>O (symmetric and antisymmetric stretching), alcohol or carboxylic acid groups [58].

A lower frequency band originating from the O–H bending modes of the H<sub>2</sub>O molecules incorporated between the lattice planes of the ReS<sub>2</sub> crystal appears at 1619.81 cm<sup>-1</sup> [59], and might overlap with the C=C stretching (alkene or aliphatic molecules) band. Alkane C–H bending mode of methyl (–CH<sub>3</sub>) group exhibits an *umbrella mode* at 1379.65 cm<sup>-1</sup> [58]. We can also identify the very weak contribution from the carbonyl group (C=O) vibrations in ketone or ester at the frequency of 1735.69 cm<sup>-1</sup> [58]. The peak linked with the S=O stretching vibrations in sulfate can be found between 1450 and 1350 cm<sup>-1</sup>, meanwhile, the SO<sub>2</sub> group asymmetric

stretch and the S=O stretch of sulfur compounds give rise to the bands in the range of 1190-1120  $\text{cm}^{-1}$  and 1060-1020  $\text{cm}^{-1}$ , respectively [58, 60].

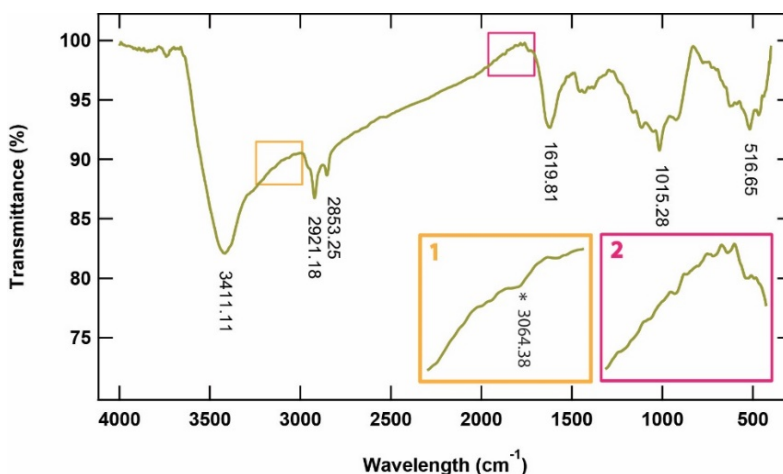


Figure 5 Infrared spectrum recorded at room temperature under ambient atmosphere.

The peak related to the  $\text{CH}_2$  wagging can be seen at the frequency of  $1159.96 \text{ cm}^{-1}$ , and the one of the C–O stretching vibration at  $1015.28 \text{ cm}^{-1}$  [58]. The C–S and S–S disulfide stretching vibrations have been assigned to the bands in the region of  $700.65\text{-}516.65 \text{ cm}^{-1}$  and  $516.65\text{-}441.09 \text{ cm}^{-1}$  [60]. The peak at  $924.48 \text{ cm}^{-1}$  is related to stretching vibrations of the H–C–S group or sulfonic acid ( $\text{HSO}_3^-$ ) [60], and the peak at  $774.31 \text{ cm}^{-1}$  to the S–OR in ester. The former band with the one at  $625.50 \text{ cm}^{-1}$  might also be attributed to the C–S stretching vibrations [58, 60]. Referring to the results from the C 1s XPS (Figure S3A) and Raman (Figure 4A curve (c)) spectra, where a clear demonstration of the  $\text{sp}^2$  bonded C species has been shown, we can assign several weak bands to the aromatic groups. Accordingly, graphitic-like species present on the sample surface gave rise to a very weak peak at  $3064.38 \text{ cm}^{-1}$  (Inset 1, Figure 5), the bands between  $2000\text{-}1700 \text{ cm}^{-1}$  (Inset 2, Figure 5) as well as the one in the range from  $1454.29$  to  $1431.04 \text{ cm}^{-1}$ , which can be ascribed to the C–H stretching, to the combination and overtone bands and to the C=C stretching modes, respectively. Finally, referring to the inorganic groups

that were determined by the XPS method, we can assign the bands appearing between 1130-1080  $\text{cm}^{-1}$  and 680-610  $\text{cm}^{-1}$  to the sulfate ( $\text{SO}_4^{2-}$ ) group vibrations [58].

### 3.1.7 Thermogravimetric analysis

The thermogravimetry (TGA) and differential thermogravimetry (DTG) analyses, spectra are shown in Figure 6A and B, revealed three major steps of the product decomposition. In the first step, from 30°C to about 600°C the weight decrease by 26.30 % is mainly due to the processes of adsorbed water loss, gaseous residues (such as CO, CO<sub>2</sub>) from the most labile carboxylate and anhydride functional groups loss (150-300°C) together with removal of the more stable oxygen groups, such as phenol and carbonyl (300-500°C). In the second step, at temperatures above 600°C, we can observe a slight increase in the rate of the sample decomposition up to 950°C, with a weight loss of 21.96%. Due to our considerations, this step can be associated with desorption and disproportionation of variously surface bonded  $\text{Re}^{6+}$  in the form of oxide [61, 62] (see discussion below).

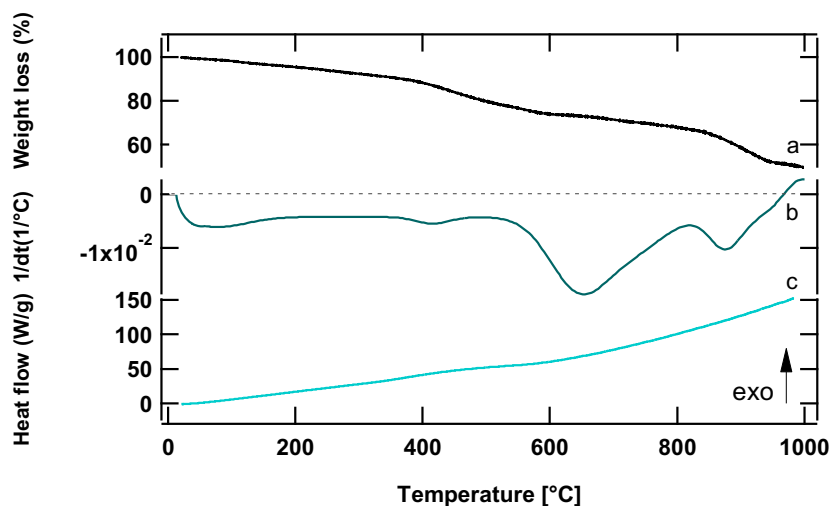


Figure 6 Spectrum of (a) TGA, (b) DTG and (c) DSC of as-synthesized  $\text{ReS}_2$  carried out under inert atmosphere.



The third and the final step is associated with the weight decrease of 8.16%, from 810 up to 1000°C and is most likely related to the evaporation of the inorganic sulfate ( $\text{SO}_4^{2-}$ ) [63], as well as to the decomposition of the  $\text{ReO}_2$ , if present ( $7\text{ReO}_{2(s)} \rightarrow 3\text{Re}^0 + 2\text{Re}_2\text{O}_7(g)$ ) [61, 64]. As it is presented in the differential scanning calorimetry (DSC) profile (Figure 6C), the exothermic characteristic points out on secondary processes taking place in the studied system, which are most likely related to the recrystallization and/or surface reconstruction of the sample upon thermal treatment.

### *3.2 Electrical characterization of the ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al memcapacitor*

The preliminary study of the electrical properties of the synthesized composite material based on the  $\text{ReS}_2$  ( $\text{ReO}_3\text{-ReS}_2$ ) were conducted in a device comprised of the active material, sandwiched between the bottom (BE, indium tin oxide (ITO)) and top (TE, aluminum (Al)) electrodes. Interestingly, as presented in Figure 7 the ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al device in contrast to the ideal memristor [65], possesses a non-zero current-voltage ( $I$ - $V$ ) crossing characteristic (point A in Figure 7), indicating coexistence of the two dynamic elements, namely resistance (memristance,  $R_m$ ) and negative capacitance (memcapacitance,  $C_m$ ) in one device [66, 67].

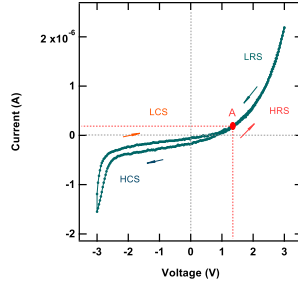


Figure 7 The  $I$ - $V$  plot of the ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al memcapacitor. Arrows indicate potential sweep direction. Sweep voltage range:  $\pm 3$ V, compliance current ( $I_{cc}$ ): 1 mA, and frequency: 10Hz.

As it is demonstrated in Figure 7, the device operates in bipolar mode, switching from a high resistance state (HRS) to a low resistance state (LRS), and subsequently from a high capacitive state (HCS) to a low capacitive state (LCS). The existence of the dynamic effect can be evidenced by the significant dependence of the device resistive and capacitive states on the scan frequency ( $\omega$ ).

As is depicted in Figure 8, at low frequencies ( $\omega = 10$  Hz) both the memristive and memcapacitive states are observed. The non-zero crossing point of the bipolar switching was determined to take place at the voltage of 1.3V corresponding to the current value of  $1.7 \times 10^{-7}$ A. What is more, the appearance of the electromotive force (*emf*) of 0.80V proves the existence of the nanobattery within the device active layer [68]. However, under an increase of the scan frequency ( $\omega \geq 100$ Hz) a substantial change in the ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al hysteresis is evidenced,

where the memristive signature completely disappears giving rise to a square-like loop featuring an entirely memcapacitive device behaviour.

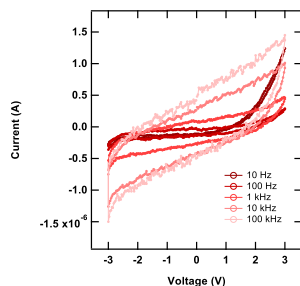


Figure 8 The  $I$ - $V$  dependence on the scan frequency of the ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al memcapacitor. Sweep voltage range:  $\pm 3$ V, and compliance current ( $I_{cc}$ ): 1 mA.

A contribution of the parasitic effect into the capacitance under the subsequent increase of the scan frequency results in a significant current instability, clearly noticeable in the case of voltage sweep at frequencies of 10 and 100 kHz (Figure 8). The increase of the frequency and in the effect an electric field ( $EF$ ) within the active material alters both the faradaic and non-faradaic processes. A transition from the memristive and memcapacitive to the purely memcapacitive state of the ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al device can be understood from the perspective of a physical transition from the ions migration within the composite layer, at slow bias sweep, to its static accumulation at very high scan frequencies. As it is expected, an apparent capacitance ( $C_{app}$ ) decreases with the increase of the scan frequency (data plot shown in Figure S7A and B) due to the limited diffusion of the ions, altering their effective interactions with the active electrode.

The numerical values of  $C_{app}$  computed for bias sweep at various scan frequencies are collected in Table S3.

#### 4. Discussion

In this study, we demonstrate a simplistic reaction between the mixture of the  $\text{NH}_4\text{ReO}_4$  and  $\text{Na}_2\text{S}\cdot 9\text{H}_2\text{O}$  occurring at room temperature, and most importantly in water solution. For this process, noncatalytic route is unsuccessful at room temperature, and the sulfidation reaction is initiated only in the presence of the Al catalyst. In the solutions of high pH value, the perrhenate ion exists as the  $\text{ReO}_4^-$  [69], meanwhile, the  $\text{Na}_2\text{S}$  dissociates to form  $\text{S}^{2-}$  and  $\text{HS}^-$  ions [70]. The adsorption of the  $\text{ReO}_4^-$  ions takes place immediately after contact of the reaction mixture with the Al catalyst surface, wherefore the sulfidation is instantly initiated. Most likely, the steric effect resulting from the change of the adsorbed  $\text{ReO}_4^-$  molecules symmetry (see Figure 4) causes the Re–O bonds polarization, which in consequence lowers the activation energy of the sulfidation process. Nonetheless, the Al catalyst role of providing an alternative mechanism of the sulfidation reaction can't be entirely ruled out. As the reaction propagates, the Al catalyst film undergoes dissolution in highly alkaline environment, following the reaction:  $2\text{Al}^0 + 2\text{OH}^- + 6\text{H}_2\text{O} \rightarrow 2[\text{Al}(\text{OH})_4]^- + 3\text{H}_{2(\text{g})}$ , to form tetrahydroxoaluminate complex ion, which exist in a solution as the  $\text{Al}(\text{OH})_4^-$  or either  $[\text{Al}(\text{H}_2\text{O})_2(\text{OH})_4]^-$  ions. After complete dissolution of the Al film, a creation of a thin layer of the product (also present in a water dispersed form) adhered to the surface of the glass substrate can be observed, along with a bubble like structures originating from the  $\text{H}_{2(\text{g})}$  and partial  $\text{NH}_{3(\text{g})}$  evolution (Figure S6). In the additional experiment, we have replaced the Al catalyst with  $\gamma$ -aluminum (III) oxide ( $\gamma\text{-Al}_2\text{O}_3$ ), however, in contrast to other reports, no catalytic effect of the  $\gamma\text{-Al}_2\text{O}_3$  has been found [27].

The sulfidation reaction is promoted by Al towards  $\text{ReS}_2$  rich in the  $\text{Re}^{6+}$  surface states, pointing out on its slightly lower selectivity toward  $\text{ReS}_2$  formation (Figure 1A). A similar phenomenon is observed in the case of S for which a noticeable amount of  $\text{S}^{6+}$  can be seen in the XPS spectrum (Figure 1B). In addition to that, high reactivity of the product surface atoms can be observed by growth of various C rich surface species, with a perceptible amount of C in the  $\text{sp}^2$  hybridisation (Figures S3A and B). Referring to the XPS analysis results (for the product before Figure 1A and after purification Figure S5A), we can distinguish a change in the surface bonding of the Re atoms by a shift of their formal oxidation state, where disappearance of the  $\text{Re}^{7+}$  ( $\text{ReO}_4^-$ ) and subsequent increase of the  $\text{Re}^{6+}$  4f photoelectron peaks is clearly demonstrated. This alteration is most likely attributable to the reduction processes of the  $\text{Re}^{7+}$  or change in the  $\text{ReO}_4^-$  group symmetry upon its interaction with surface atoms [51]. Accordingly, several bands present in the Raman spectrum (Figure 4A curve (c)), have been previously identified as bending modes of the O–Re–O linkages in the  $\text{Re}^{6+}$  oxide ( $\text{ReO}_3$ ) as well as lower crystal symmetry  $\text{ReO}_3$  [45, 46]. Moreover, earlier studies have shown a strong reactivity of the  $\text{ReO}_3$  surface towards the dissociation of atmospheric compounds, such as  $\text{CO}_2$  and  $\text{H}_2\text{O}$  [49, 55, 62]. Its reactivity could explain surface alteration, through the occurrence of the secondary reactions with gaseous molecules dissolved in water, taking place during the sample purification process.

The aforementioned is evinced in the emergence of the extended delocalized electrons peak in the C 1s XPS spectrum (Figure S3A) as well as carbon D and G bands in the Raman spectrum (Figure 4A curve (c)). Referring to the latter, the  $\text{ReO}_4^-$  and  $\text{ReO}_3$  are highly soluble in water and the observable disappearance of the  $\text{Re}^{7+}$  and presence of the  $\text{Re}^{6+}$  4f photoelectron peaks (XPS spectra Figures S5A and 1A, respectively) confirms the existence of  $\text{Re}^{6+}$  in a form of surface bonded molecules. The change of the  $\text{Re}^{7+}$  to  $\text{Re}^{6+}$  coordination, thus in effect molecule

symmetry, can be understood not only from the shift of the highest frequency Raman peaks but also from the more complicated spectrum of the fundamental Raman bands for which splitting, broadening and overlap is evidenced. These transitions result from the complex environment of the  $\text{Re}^{6+}$ , presumably a combination of surface bonded  $\text{ReO}_4^-$ ,  $\text{ReO}_3$ ,  $\text{Re}_2\text{O}_7$  and possibly other, implying uncertain bands designation which remains open to discussion and further interpretation [44, 49, 50, 62, 71].

Taking under consideration the experimental results, the resistance switching of the ITO/ $\text{ReO}_3$ - $\text{ReS}_2$ /Al memcapacitor is postulated to be governed by geometrical (redox reactions: electrochemical metallization (ECM) process) or permittivity (permittivity switching, ionic doping) related mechanism. In principle, the ECM occurs in the devices where the electrochemically active electrode ions contribute to the conducting filaments (CFs) formation [72, 73]. The Al electrode electrochemical activity should be also accounted while considering the physical principles of operation of the ITO/ $\text{ReO}_3$ - $\text{ReS}_2$ /Al memcapacitor. The application of the positive bias voltage to the active electrode might induce its anodic dissolution, field-driven migration of the cations in the ion conductive phase towards BE, and finally their reduction at the inert ITO counter electrode surface. The following electro-crystallization process leads to the growth of the CFs in the direction of the TE, hence switching the device into the LRS owing to the facilitated charge conduction within the developed CFs. This mechanism was identified in the mixed electronic and ionic conductivity materials, usually utilizing either Ag or Cu as the active electrode [74, 75]. However, in the ITO/ $\text{ReO}_3$ - $\text{ReS}_2$ /Al memcapacitor, the high resistance ON state ( $R_{\text{ON}} \sim 1.38 \text{ M}\Omega$ , Figure 7) might indicate the formation of CFs without a galvanic contact with the active electrode (Al TE). This explanation is further supported by the lack of the observation of the ohmic charge carrier conduction under positive bias voltage scan (derived

from  $\log J$  vs.  $\log V$  plot, data not shown here), representing charge carrier conduction through formed CFs (the  $J \propto V^n$  relation fitted slope values,  $n$ , were found to be  $<0.1$ ). In effect, the possible charge conduction from the tip of the CF towards TE would have to be governed by the quantum mechanical tunneling.

Another possible explanation of the memcapacitor operation could be related to the polarization effect, in which the redistribution of the charges within the internal layer gives rise to an internal  $EF$  that opposes the external  $EF$  of the charged plates. This internal electric field may over screen the external field, resulting in a negative capacitance observed in the studied device [76, 77]. Moreover, as a support to the above mentioned, the existence of the nanobattery ( $emf$ ) is observed due to the instance of the charge separation within the active material. Synthesized in this study composite material (for details please refer to the EDX and XPS results) possesses inhomogeneous phase distribution, comprised of the crystalline grains surrounded by the grain boundaries of complex chemical composition. These phases are expected to exhibit, to the certain extent, apart from electronic also ionic conduction. It is worth to mention, that in addition to the unique combination of memristor and memcapacitor, presented here device also manifests self-rectification. Presented in this study memcapacitor can be relatively easy fabricated, however in order to achieve a wide range of capacitances a full understanding of the fundamentals of the ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al device operation is essential, particularly from the perspective of the dynamic changes taking place in its active layer, thus more comprehensive studies are indispensable.

## 5. Conclusion

In summary, this study presents the room temperature sulfidation process of the NH<sub>4</sub>ReO<sub>4</sub> carried out by the Na<sub>2</sub>S·9H<sub>2</sub>O. It has been shown, that the reaction takes place in a water solution

due to the catalytic role of the Al, and leads to the creation of ReS<sub>2</sub> rich in the surface Re<sup>6+</sup>, S<sup>6+</sup>, and sp<sup>2</sup> C states. The wet chemical synthesis is easily scalable and most importantly presents a new approach towards bottom up synthesis of the ReS<sub>2</sub> based composite material. Moreover, a demonstration of the unique combination of memristor and memcapacitor in the fabricated ITO/ReO<sub>3</sub>-ReS<sub>2</sub>/Al device indicates that the active material holds promise for its application in the emerging field of memristor technology.

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### **Appendix A. Electronic Supporting Information**

Information regarding the results and discussion of SEM, XPS, X-ray diffraction pattern data analysis, fitted Raman modes frequencies, and capacitance dependence on the scan frequency of the memcapacitor are presented in the electronic supporting information.

### **Declaration of Competing of Interest**

The authors claim no competing of interest.

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